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Customer No.: 31561
Application No.: 10/064,208
Docket No.: 8309-US-PA

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:

CHEN

Serial No. : 10/064,208

Filed : 06/21/2002

For : SUBSTRATE EXPOSURE
APPARATUS AND METHOD

Examiner : Christopher G.
Young

Art Unit : 1756

Docket No. : 8309-US-PA

No fee is believed to be due. However, the Commissioner is authorized to charge any fees required in connection with the filing of this paper to account No. 50-2620 (Order No. 8309-US-PA).

AMENDMENTS AND RESPONSE TO OFFICE ACTION

U.S. Patent and Trademark Office
Commissioner for Patents
2011 South Clark Place
Customer Window, Mail Stop Non-Fee Amendment
Crystal Plaza Two, Lobby, Room 1B03
Arlington, Virginia 22202

Dear Sir:

In reply to the Office Action dated June 26, 2003, Applicants submit the following Amendments and Remarks.

10/06/2003 CSTAS1 00000006 502620 10064208
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AMENDMENTS

Please amend the application as indicated hereafter.

In the Claims:

1 (withdrawn). A substrate exposure apparatus, applicable to transfer a pattern to a photoresist on a surface of a substrate, the substrate exposure apparatus comprising:

a scan light source, disposed at a position spaced from a surface of the photoresist on the substrate with a distance, and the scan light source comprising a plurality of point light sources; and

a scan control system, converting the pattern into a timing signal to control light and dark status of each of the point light sources at different times, the scan control system further allows the substrate exposure apparatus to have a scan function, such that the scan light source scans the photoresist at least once along a scan path for exposure.

2 (withdrawn). The substrate exposure apparatus according to claim 1, wherein the substrate includes a printed circuit board.

3 (withdrawn). The substrate exposure apparatus according to claim 1, wherein the substrate includes a wafer.

4 (withdrawn). The substrate exposure apparatus according to claim 1, wherein the substrate includes various types of package substrates.

5 (withdrawn). The substrate exposure apparatus according to claim 1, wherein the point light sources are arranged into one line light source.